

ECE115C – Digital Electronic Circuits

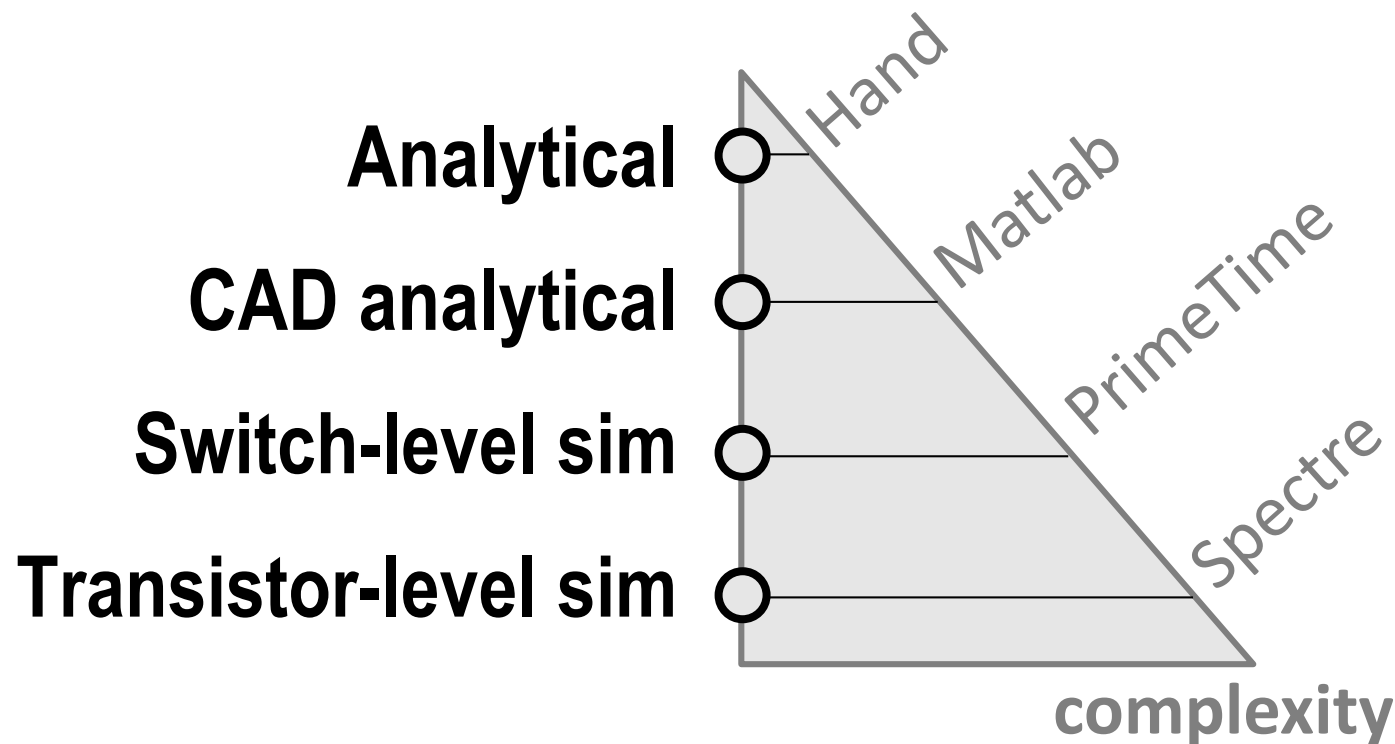
Lecture 2: MOS Transistor: IV Model



115C vs. 189 Material

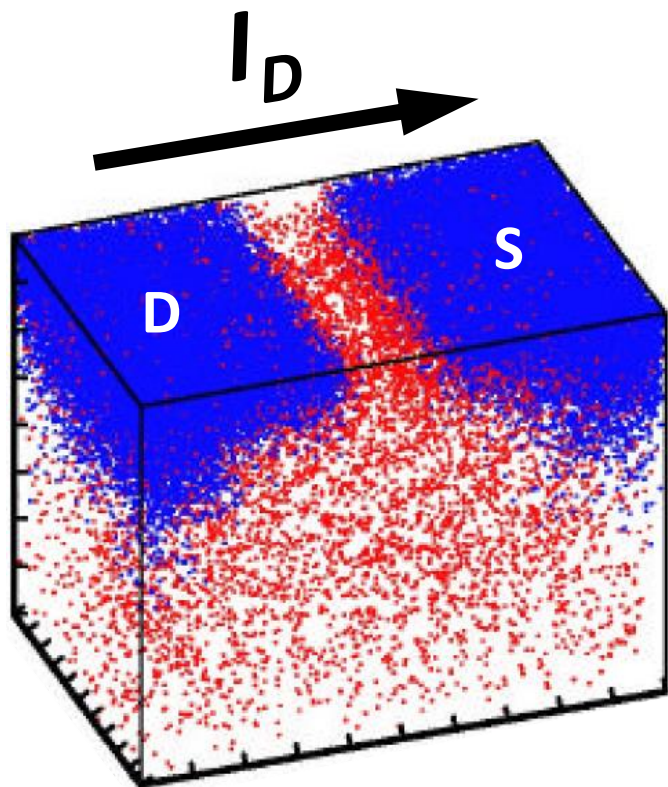
- ◆ Content marked with **189** indicates material that is optional in 115C and required in 189
- ◆ If **189** is in the slide title, it applies to the entire slide
- ◆ 115C students will have access to all **189** information as an additional resource and optional study
- ◆ 115C project will not require layout
 - 115C students will get layout experience on a relevant digital block (e.g. full adder cell)
- ◆ 189 students are required to do layout in their project

Levels of Modeling



Different **complexity**, **accuracy**, speed of convergence...

MOS Transistor Modeling

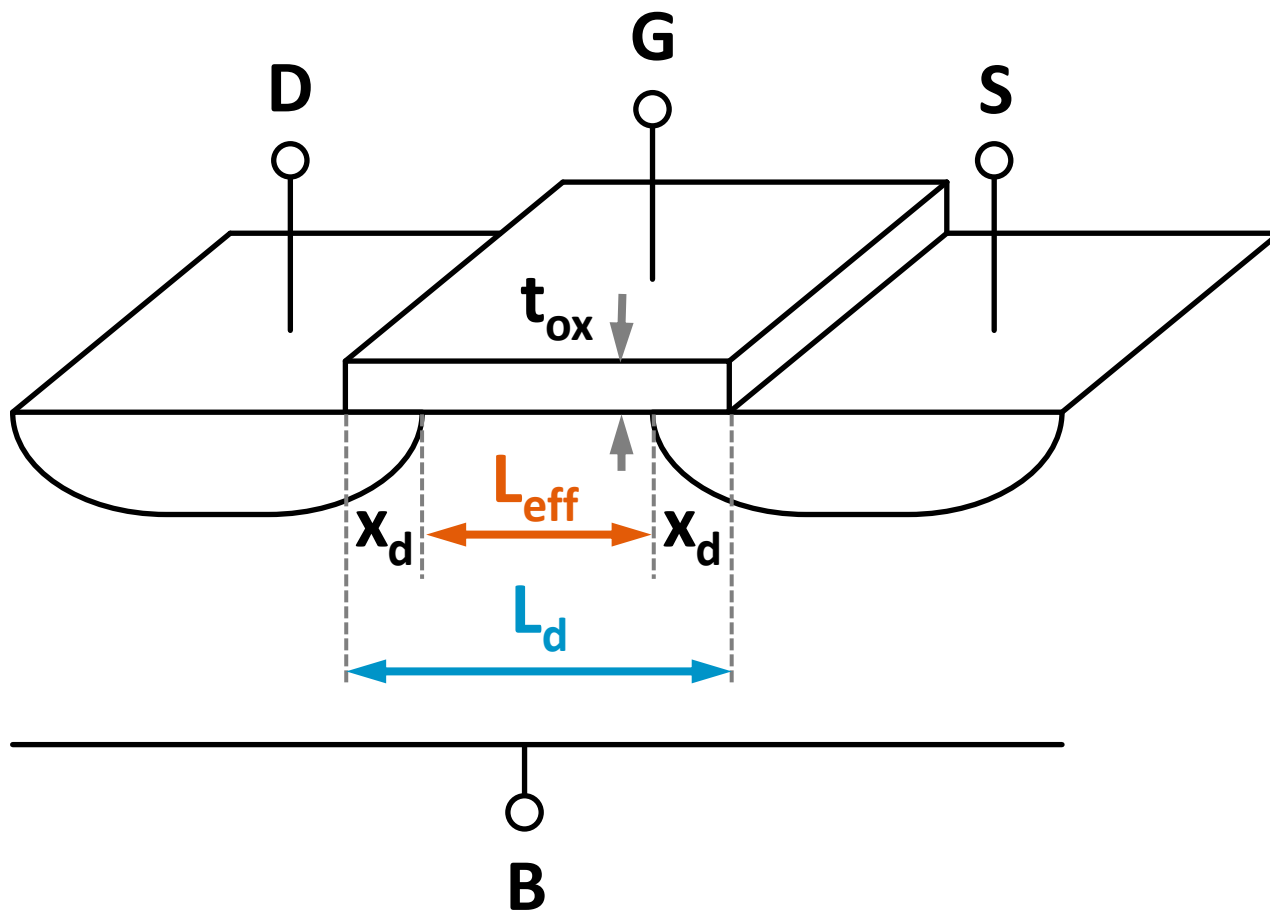


Our goal is to model
delay and energy

not current

But have to start
with current

MOSFET, Notations



Hand-analysis I-V formulas:

$$L = L_{eff}$$

Important Concepts to Understand

- 189 ♦ Threshold voltage (V_T)
- ♦ Velocity saturation
- ♦ Channel length modulation

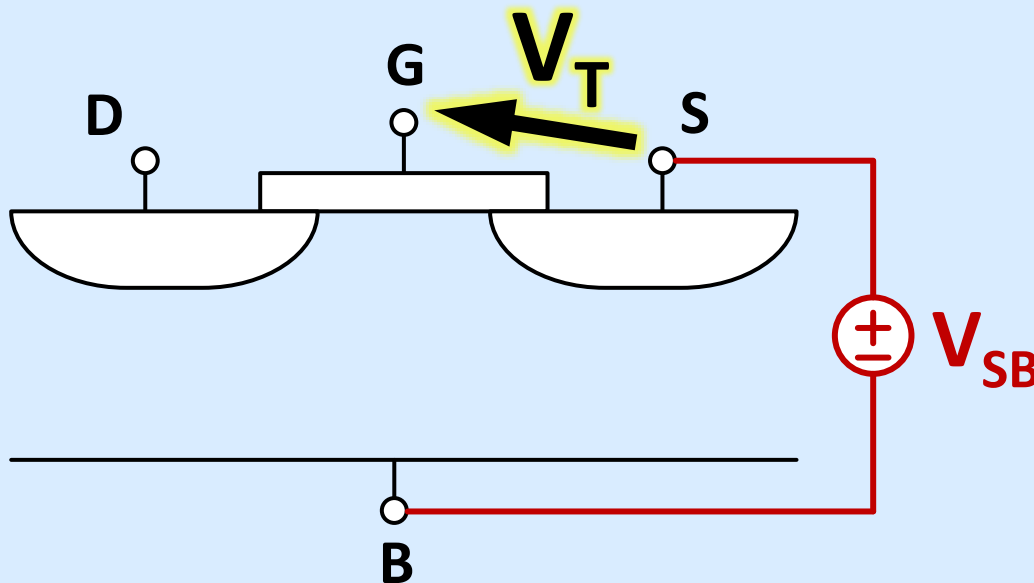
Threshold Voltage, V_T

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$$V_{SB} = 0$$

V_{T0} is approx 0.2V for our process

$$V_T = V_{T0} + \gamma \cdot (\sqrt{|-2\Phi_F + V_{SB}|} - \sqrt{|2\Phi_F|})$$



NMOS:

- ◆ $V_{SB} > 0$ (RBB)
- ◆ $V_{SB} < 0$ (FBB)

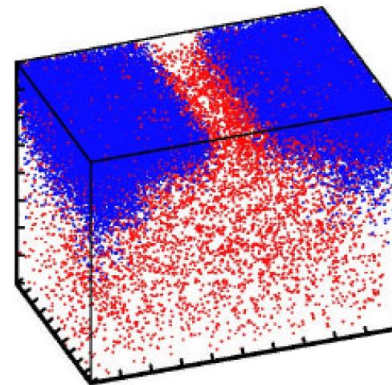
PMOS:

- ◆ $V_{SB} > 0$ (FBB)
- ◆ $V_{SB} < 0$ (RBB)

Outline

◆ MOS Transistor

- Basic Operation
- Modes of Operation
- Deep sub-micron MOS



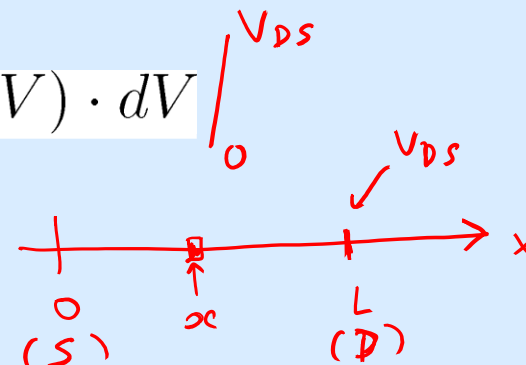
The Drain Current in Linear Regime

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- Combining velocity and charge:

$$I_D \cdot dx \Big|_0^L = \mu_n \cdot C_{ox} \cdot W \cdot (V_{GS} - V_T - V) \cdot dV \Big|_0^{V_{DS}}$$

- Integrating over the channel:



$$I_D = \underbrace{\mu_n \cdot C_{ox}}_{k'_n} \cdot \underbrace{\frac{W}{L}}_{k_n} \cdot \left[(V_{GS} - V_T) \cdot V_{DS} - \frac{V_{DS}^2}{2} \right]$$

Transconductance: $k'_n = \mu_n \cdot C_{ox}$

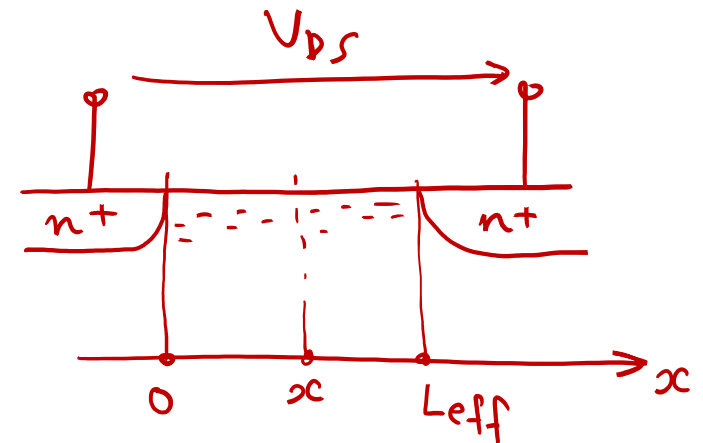
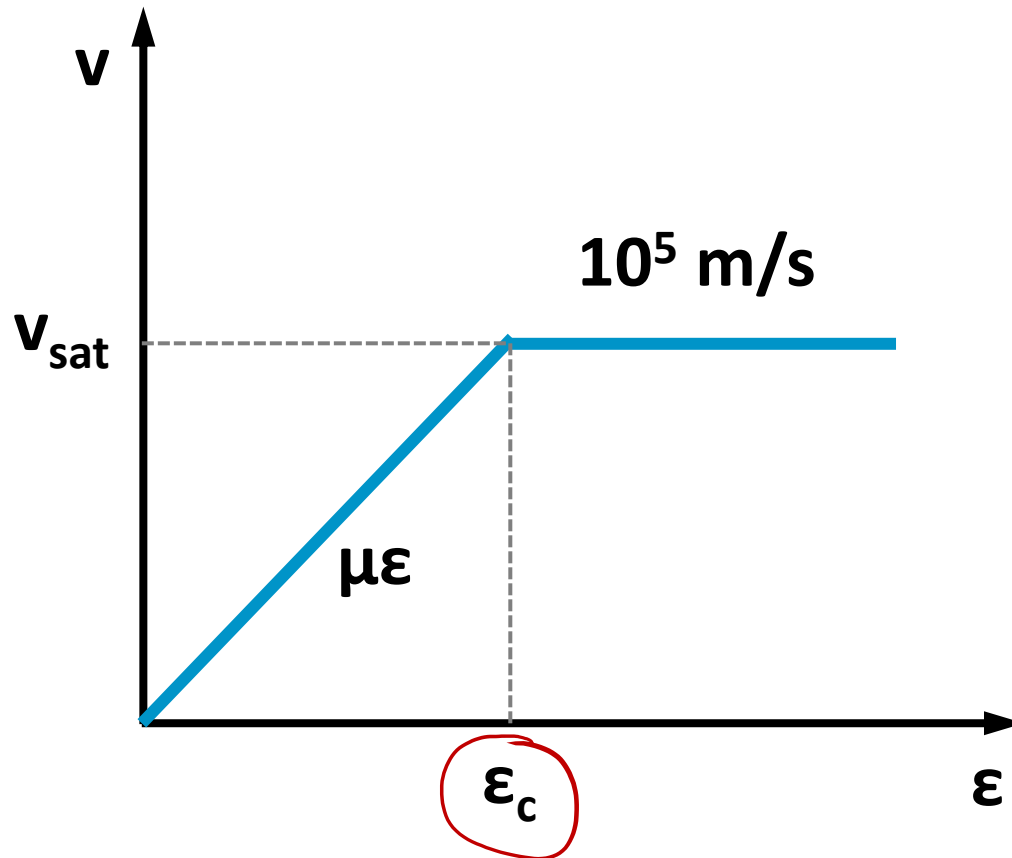
Gain factor: $k_n = k'_n \cdot \frac{W}{L}$

Small $V_{DS} \rightarrow$ ignore quadratic term $\rightarrow$ **linear** V_{DS} dependence

$L =$ effective $L = L_d - 2x_d$

Velocity Saturation

- Carrier velocity saturates when critical field is reached



$$\epsilon = \frac{V_{DS}}{L_{eff}}$$

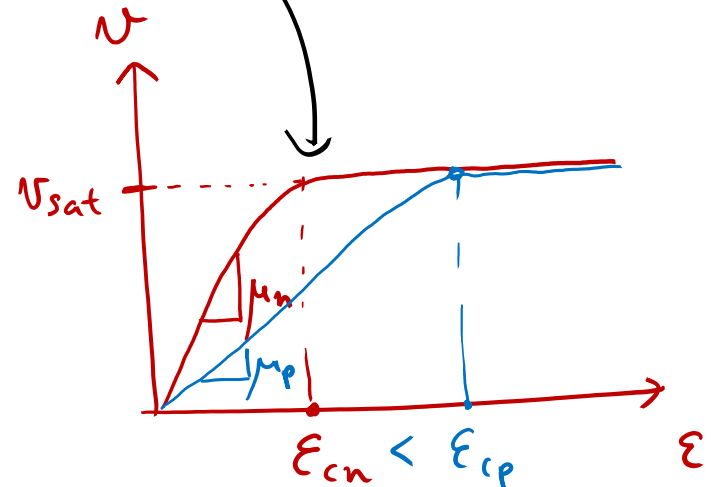
Simple Model

$$v_n = \frac{\mu \epsilon}{1 + \epsilon / \epsilon_c}, \quad \epsilon \leq \epsilon_c$$

$$v_n = v_{sat}, \quad \epsilon \geq \epsilon_c$$

Continuity @ $\epsilon = \epsilon_c$

$$v_{sat} = \frac{\mu_n \cdot \epsilon_c}{2}$$



$$v_n^{sat} = v_p^{sat}$$

$$\epsilon_{cn} < \epsilon_{cp}$$

◆ Approximate velocity:

$$v_n = \frac{\mu_n \cdot \xi}{1 + \xi/\xi_c} \quad \text{for } \xi \leq \xi_c$$

$$v_n = v_{sat} \quad \text{for } \xi \geq \xi_c$$

A more general model:

$$v_n = \frac{\mu_n \cdot \xi}{(1 + (\xi/\xi_c)^n)^{1/n}}$$

we use $n = 1$

◆ And integrate current again:

$$I_D = \frac{\mu_n \cdot C_{ox}}{1 + \frac{V_{DS}}{\xi_c \cdot L}} \cdot \frac{W}{L} \cdot \left[(V_{GS} - V_T) \cdot V_{DS} - \frac{V_{DS}^2}{2} \right]$$

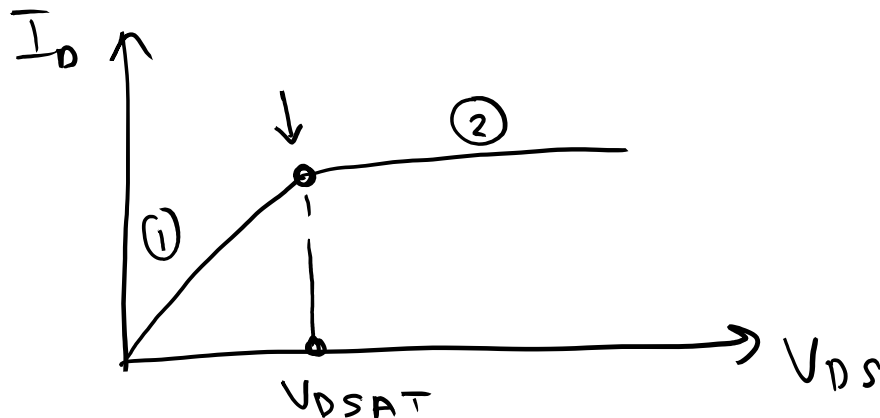
In **deep submicron**, there are three regions of operation:
(1) cutoff, (2) resistive (linear), and (3) **velocity saturation**

Including Velocity Saturation in the I_D Formula

$$\textcircled{1} \quad I_D = \frac{\mu_n \cdot C_{ox}}{1 + \frac{V_{DS}}{E_c \cdot L}} \cdot \frac{W}{L} \left[\underbrace{(V_{GS} - V_T)}_{V_{GT}} \cdot V_{DS} - \frac{V_{DS}^2}{2} \right] = I_{DSAT} \quad @ V_{DS} = V_{DSAT}$$

$$\textcircled{2} \quad I_{DSAT} = v_{sat} \cdot C_{ox} \cdot W [V_{GS} - V_T - V_{DSAT}]$$

$\uparrow$
 $\frac{\mu_n E_c}{2}$ (continuity of $v(E)$ model)



Calculating Velocity Saturation, V_{DSAT}

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$$\textcircled{1} = \textcircled{2} \Rightarrow \cancel{\frac{\mu_n \epsilon_c}{2}} \cancel{C_{ox}} \cancel{W} \cdot (V_{GT} - V_{DSAT}) = \cancel{\frac{\mu_n C_{ox}}{1 + \frac{V_{DSAT}}{\epsilon_c L}}} \cancel{\frac{W}{L}} \left[V_{GT} \cdot V_{DSAT} - \frac{V_{DSAT}^2}{2} \right]$$

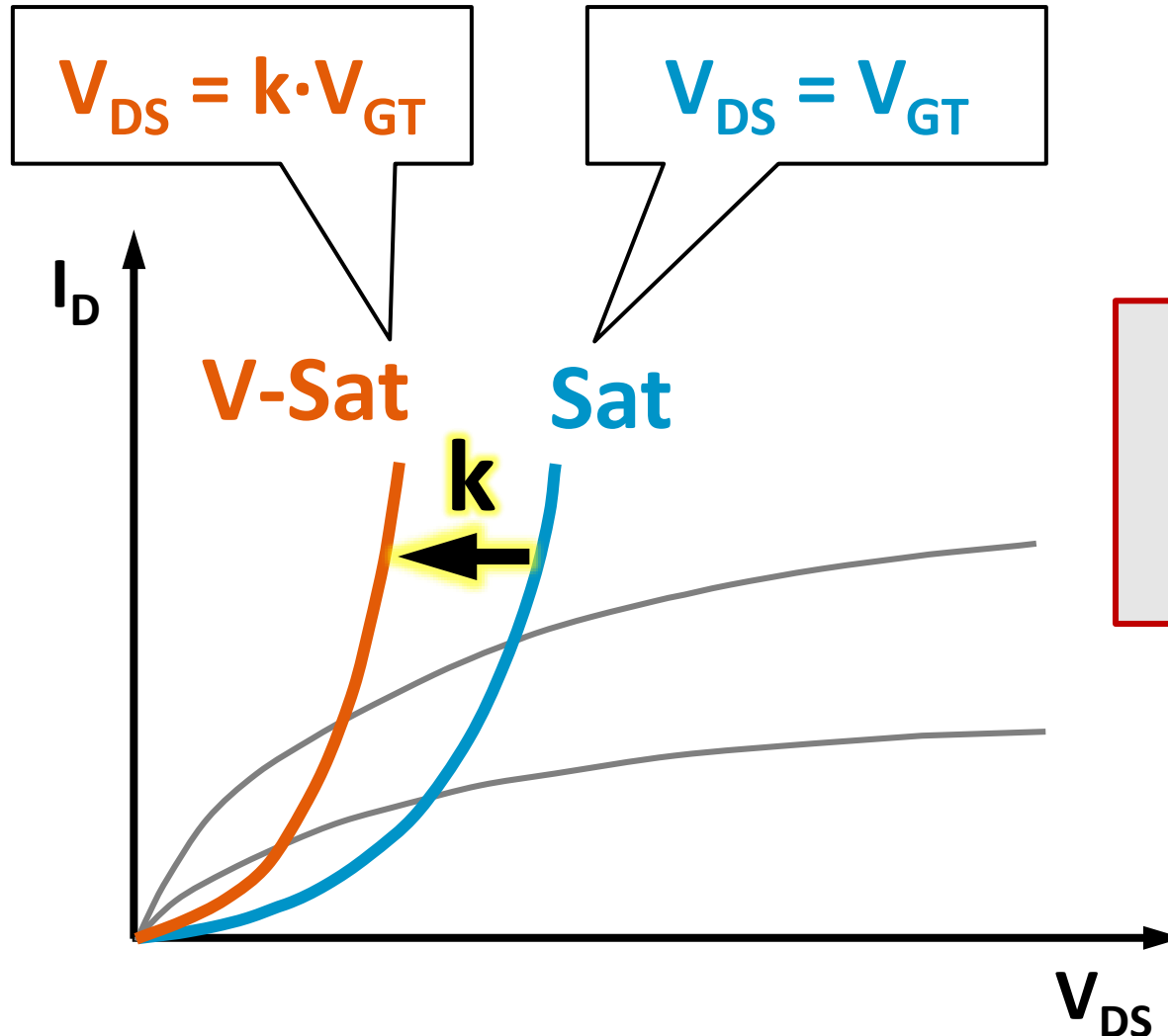
$$\left(\frac{\epsilon_c L}{2} + \frac{V_{DSAT}}{2} \right) (V_{GT} - V_{DSAT}) = V_{GT} \cdot V_{DSAT} - \frac{V_{DSAT}^2}{2}$$

$$\frac{\epsilon_c L}{2} V_{GT} - \frac{\epsilon_c L}{2} V_{DSAT} - \frac{V_{GT} V_{DSAT}}{2} = 0$$

$$V_{DSAT} = \frac{V_{GT}}{1 + \frac{V_{GT}}{\epsilon_c L}} = \underbrace{K(V_{GT})}_{< 1} \cdot V_{GT}$$

$$K(V_{GT}) = \frac{1}{1 + \frac{V_{GT}}{\epsilon_c L}} < 1$$
$$< V_{GT} - V_T$$

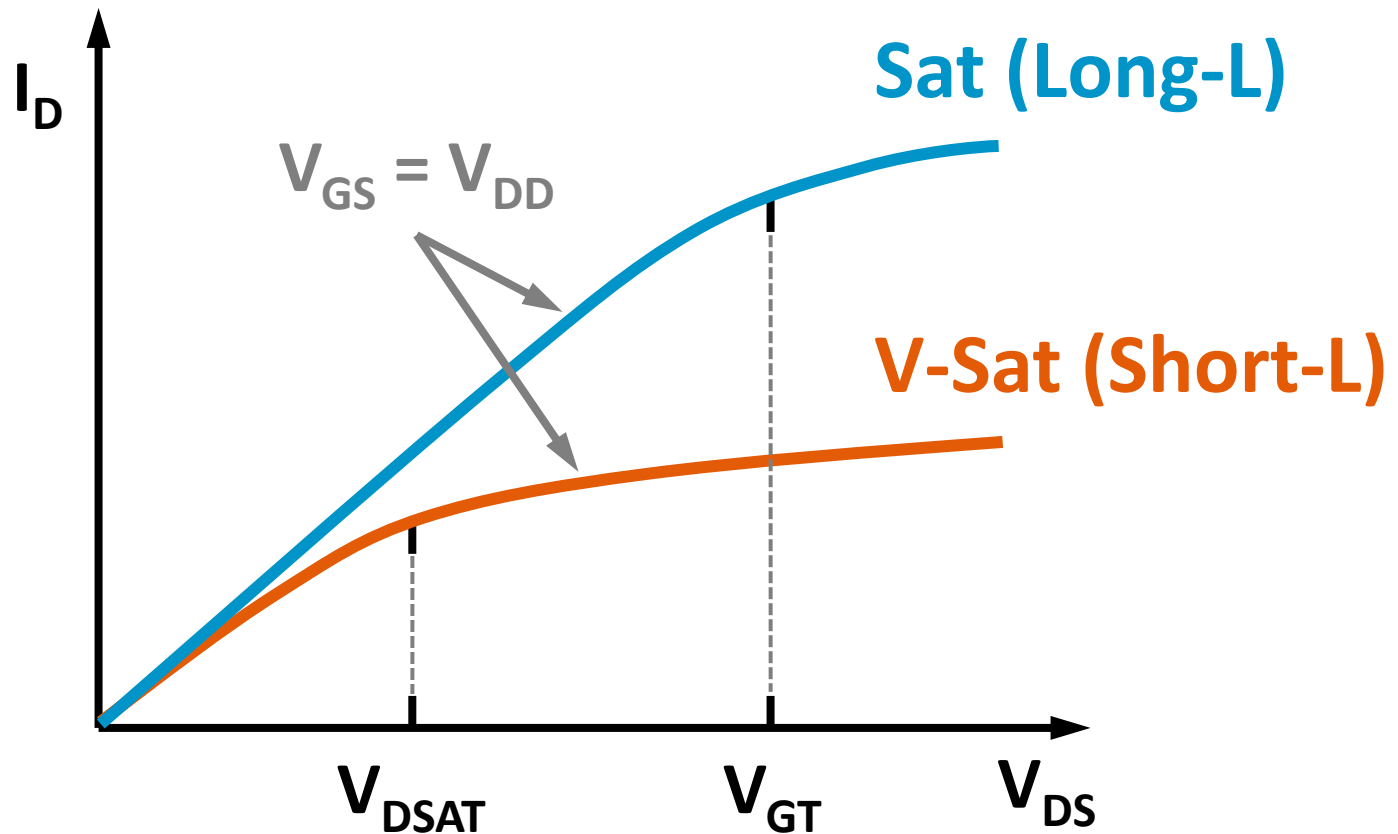
V-Sat Occurs at LOWER V_{DS} than Sat



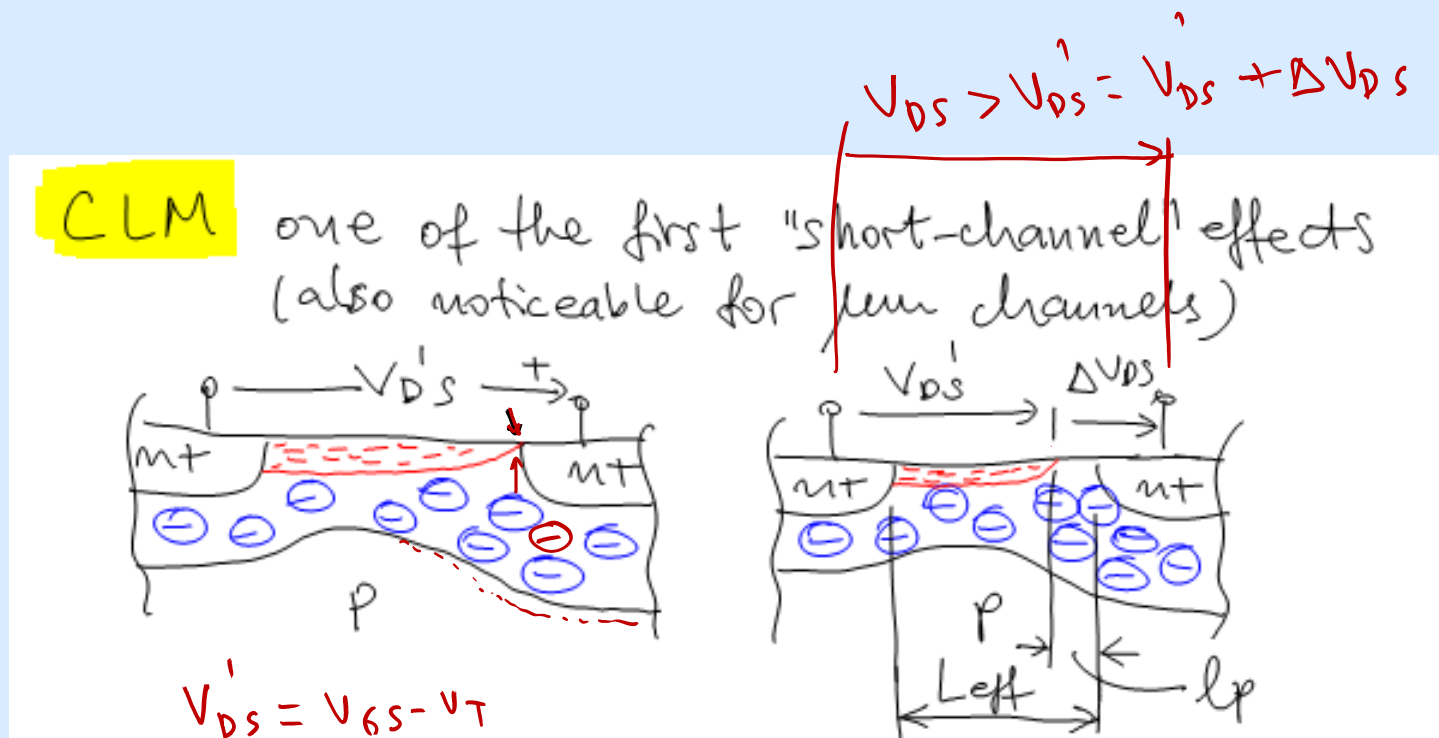
$$k = \frac{1}{1 + \frac{V_{GT}}{\epsilon_c \cdot L}}$$

$$k = k(V_{GT})$$

V-Sat: Less Current for Same V_{GS}



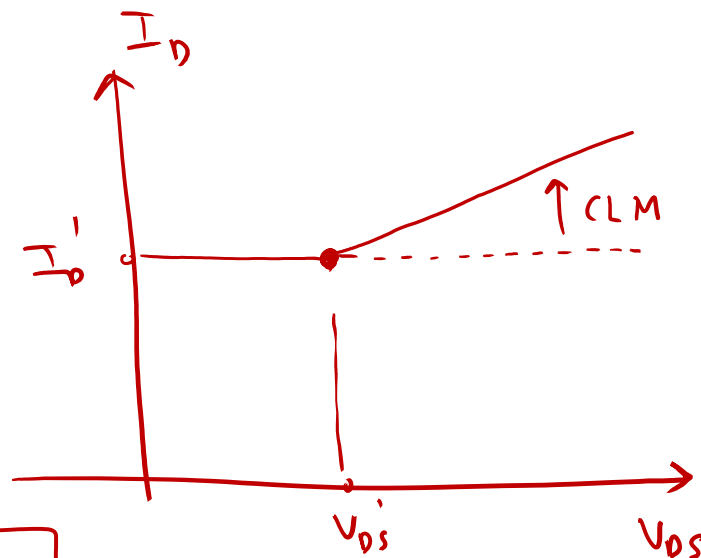
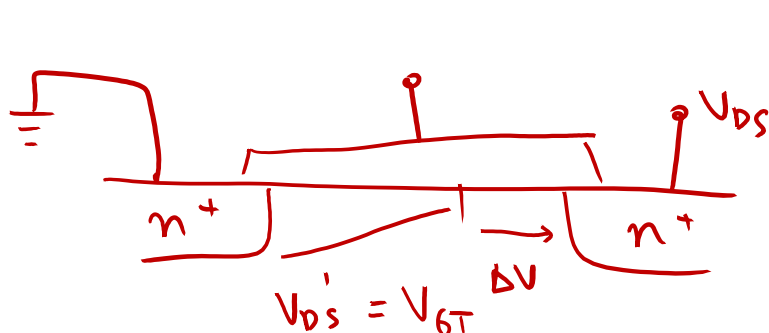
◆ Channel pinch-off



Modeling Channel Length Modulation (CLM)

◆ Many empirical models

- Goal: get a simple model that is convenient for hand analysis



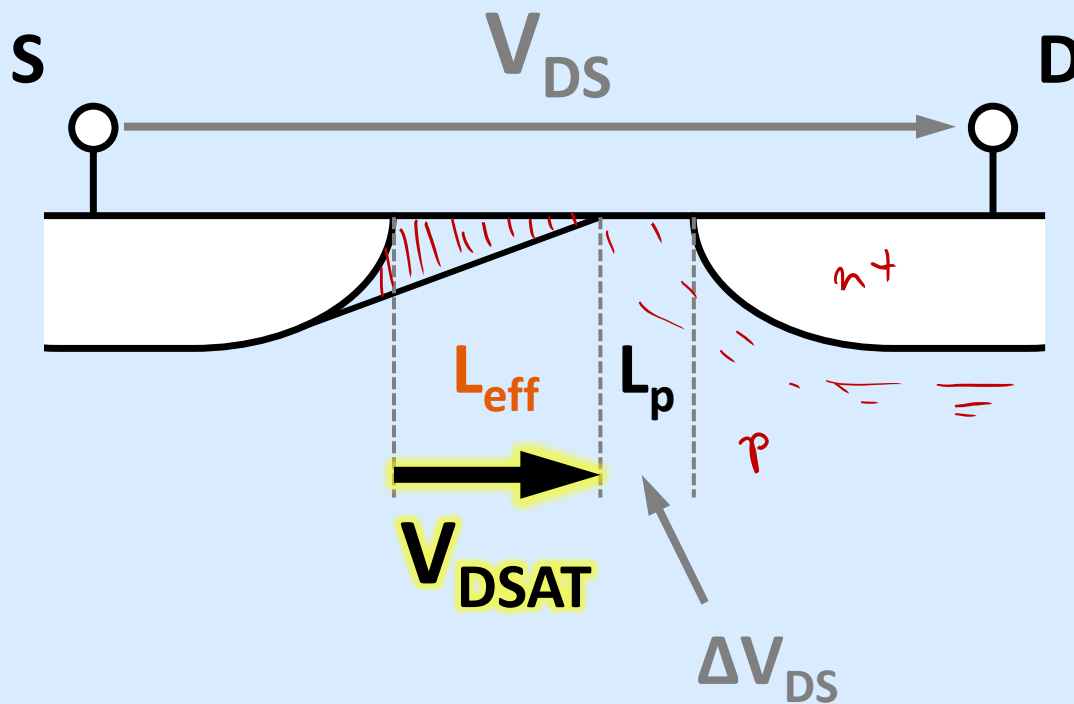
$$I_D = I_D' \cdot (1 + \lambda \cdot V_{DS})$$

CLM parameter

CLM Holds in V-Sat

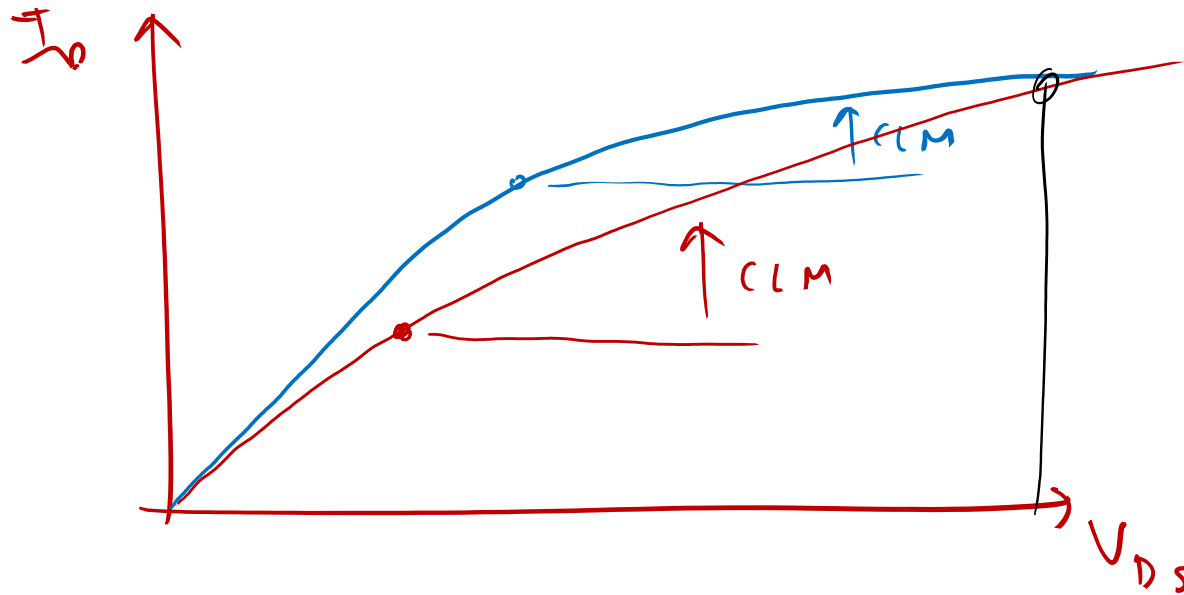
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$$V_{DS} > V_{DSAT}$$



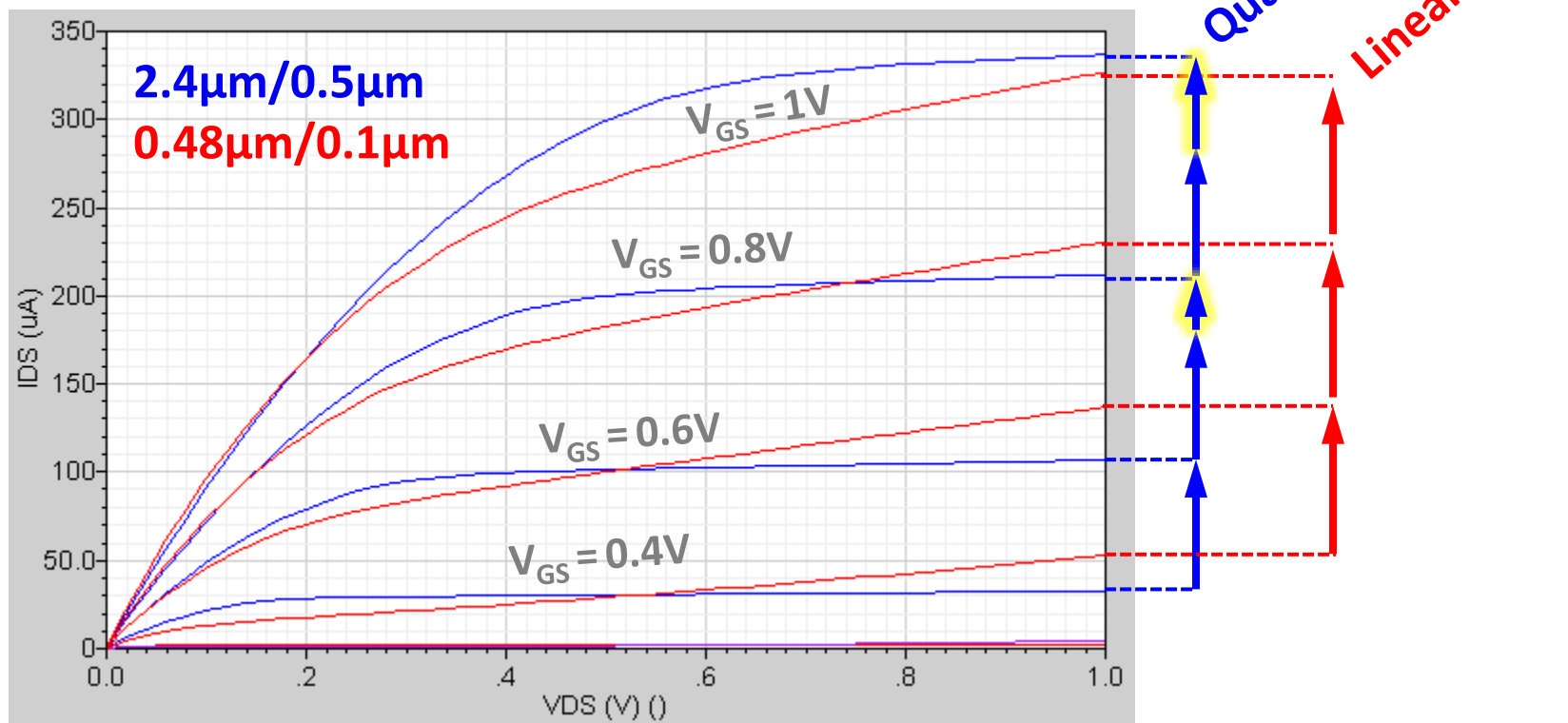
Saturation vs. Velocity Saturation

- ◆ V-Sat occurs for lower V_{DS} than Sat

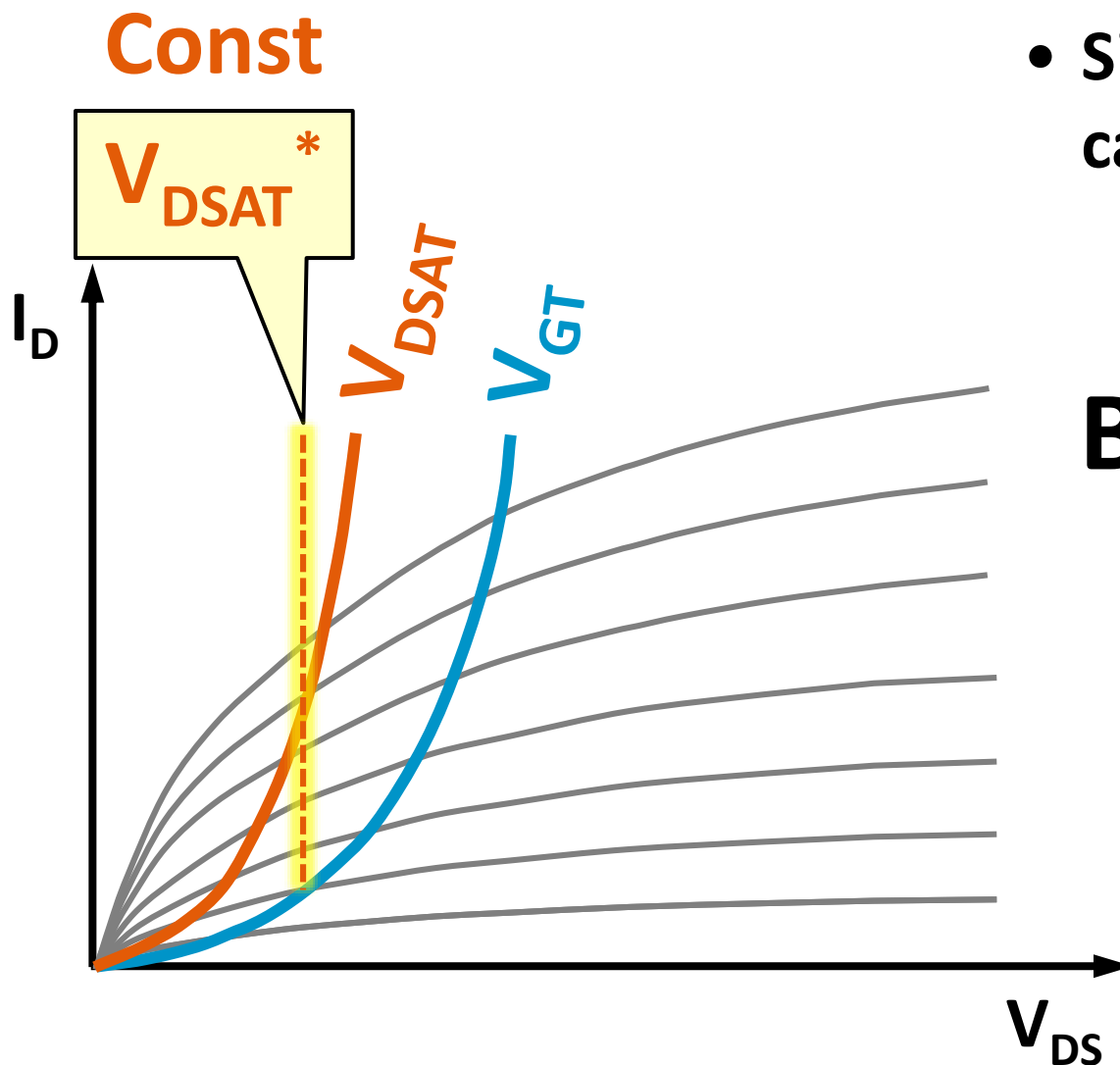


Simulation: Long vs. Short Channel (90nm)

- ◆ $I_D^{V_{\text{Sat}}}(V_{\text{GS}})$ linear, $I_D^{\text{Sat}}(V_{\text{GS}})$ quadratic
- ◆ Stronger CLM in short-L than long-L
- ◆ $I_D^{V_{\text{sat}}} < I_D^{\text{Sat}}$ only for large V_{GS}



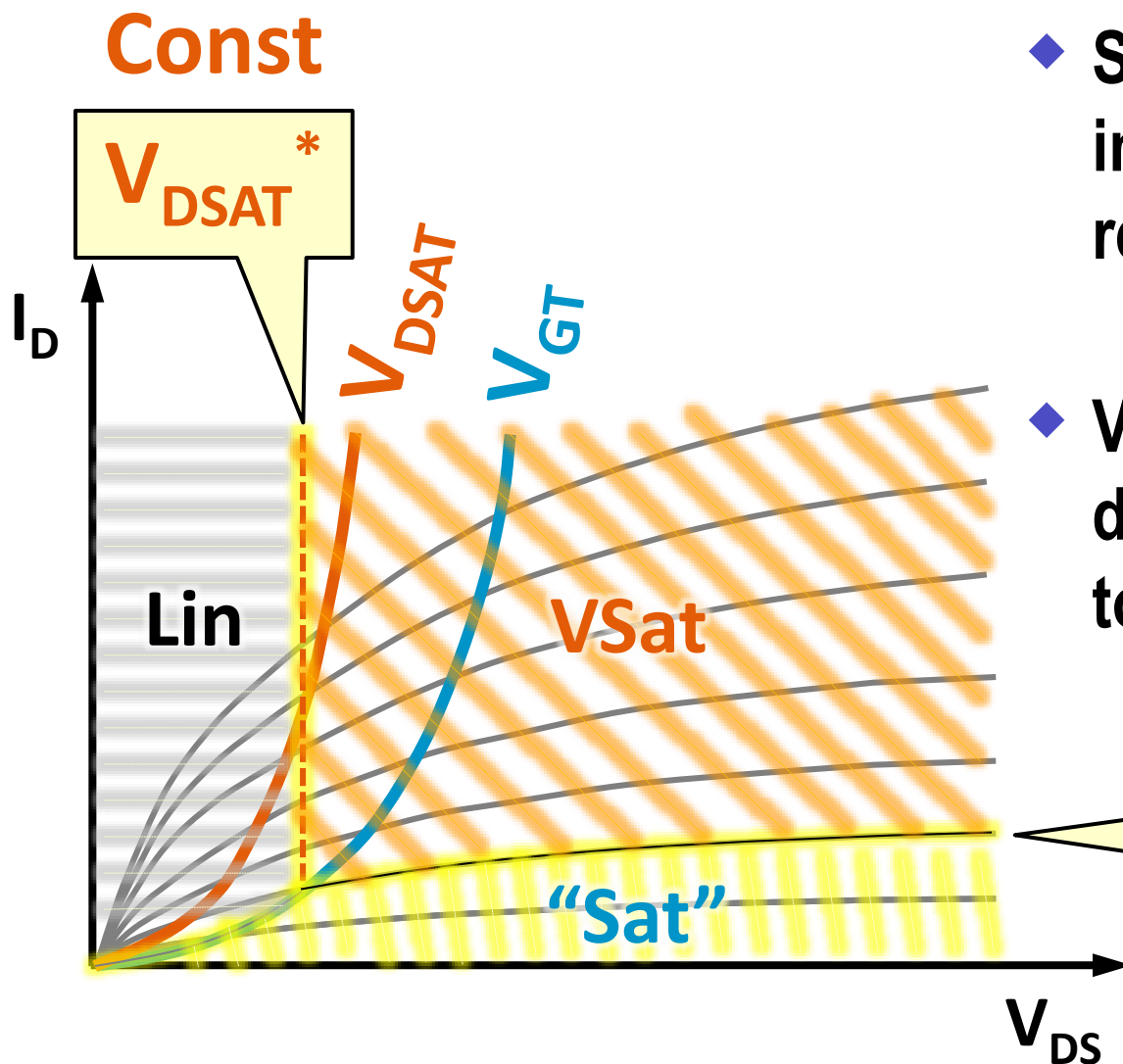
Simplification: $V_{DSAT} = \text{Constant}$



- Simplifies hand calculations

BUT...

Regions of Operation



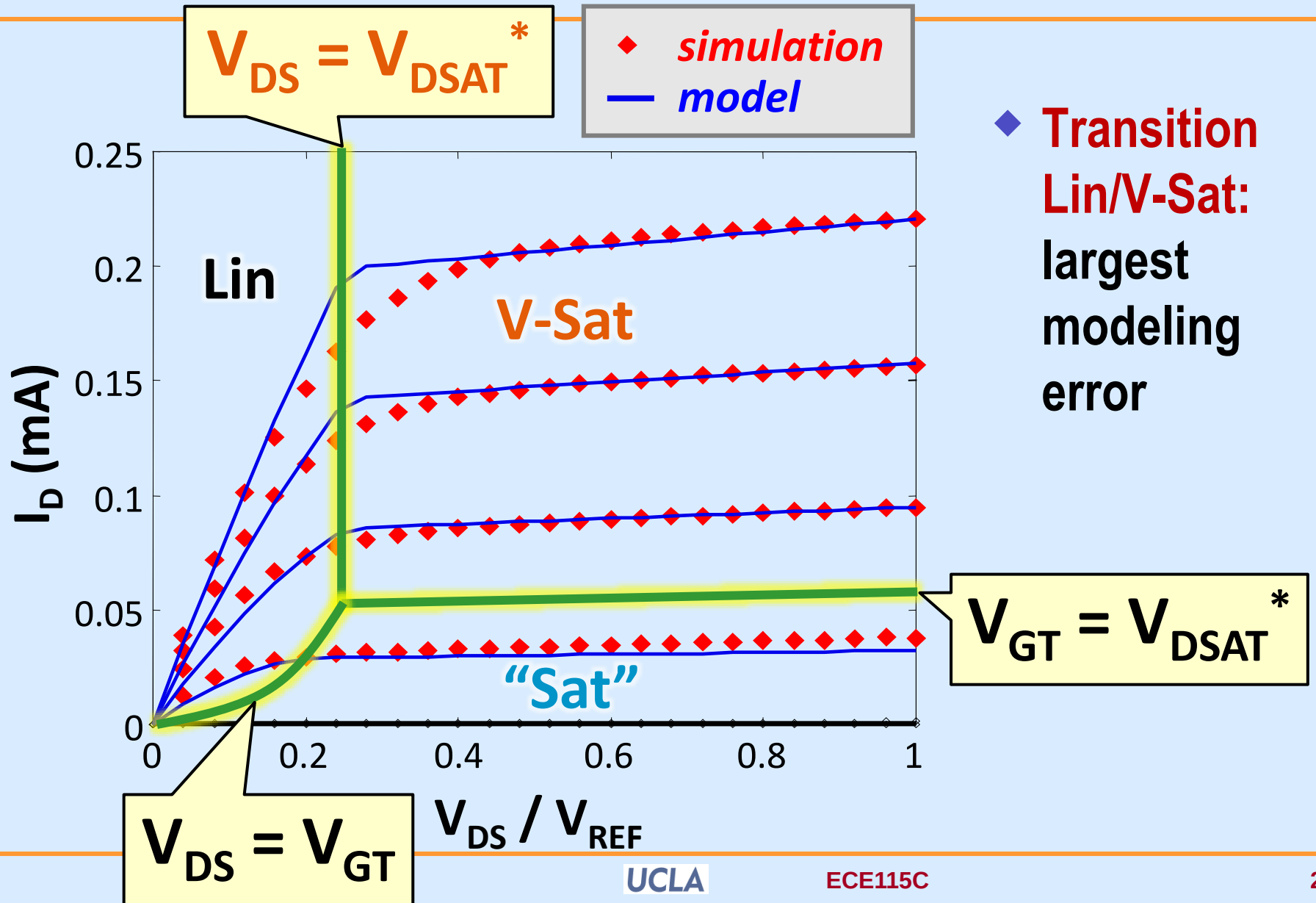
◆ Simplification introduces "Sat" region for low V_{GS}

◆ $V_{GT} < V_{DSAT}$, the device appears to be in "Sat"

$$V_{GT} = V_{DSAT}^*$$

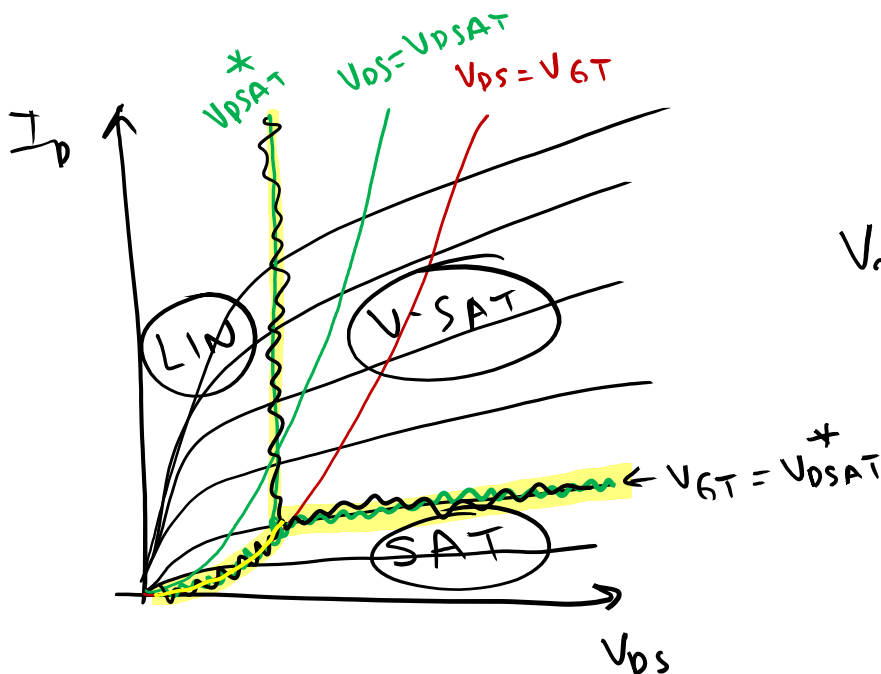
Unified Model vs. SPICE Simulation

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MOS Regions of Operation

- ◆ **Nano-scale MOS devices operate in velocity saturation**
 - Saturation still possible for low V_{GS} values (up to V_{DSAT})

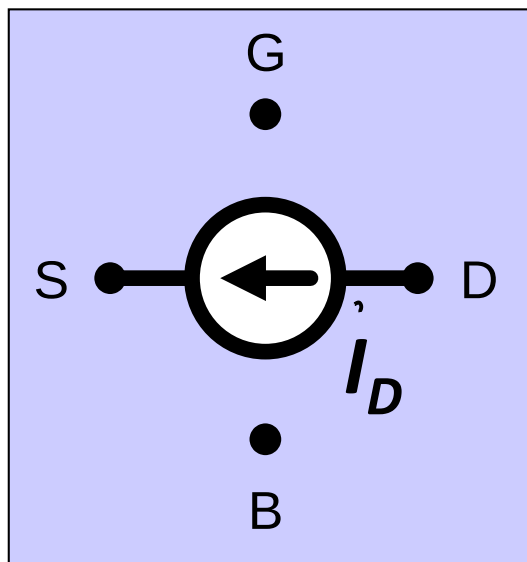


$$V_{min} = \min \left\{ V_{GS}, V_{DS}, V_{DSAT}^* \right\}$$

↑ ↑ ↑
"SAT" LIN V-SAT

MOS I-V Model: Active Region

$$V_{GT} = V_{GS} - V_T$$



Active region ($V_{GT} \geq 0$) Lin, Sat, V-Sat

$$I_D = k' \cdot \frac{W}{L} \cdot \left(V_{GT} \cdot V_{min} - \frac{V_{min}^2}{2} \right) \cdot (1 + \lambda \cdot V_{DS})$$

$$V_{min} = \min(V_{DS}, V_{GT}, V_{DSAT}^*)$$

$\uparrow$ $\uparrow$ $\uparrow$
Lin "Sat" V-Sat

Neglect CLM in linear region

Model Parameters: Active Region

V_{T0} : Threshold voltage
 γ : Body effect
 V_{DSAT}^* : Velocity saturation
 k' : Transconductance ($k' = \mu \cdot C_{ox}$)
 λ : Channel-length modulation (CLM)

- CLM term ($1 + \lambda V_{DS}$) also included for linear region
 - Empirical, no physical justification

Typical Values for 90nm

- ◆ $\epsilon_{ox} \cdot \epsilon_0 = 3.5 \cdot 10^{-11} \text{ F/m}$ ($\epsilon_{ox} = 3.9$)
- ◆ $t_{ox} = 2.3 \text{ nm}$
- ◆ $C_{ox} = \epsilon_{ox} / t_{ox} = 15.2 \text{ fF}/\mu\text{m}^2$

- ◆ For $W/L = 430\text{nm}/120\text{nm}$
- ◆ $C_g = 0.65 \text{ fF}$ $\nwarrow x_d = 15 \text{ nm}$

- ◆ $L_{eff} = 70 \text{ nm}$
- ◆ $\epsilon_c = 4 \text{ V}/\mu\text{m}$ $\swarrow$
- ◆ $V_{DSAT}^* = \epsilon_c L = \underline{\underline{0.3 \text{ V}}}$

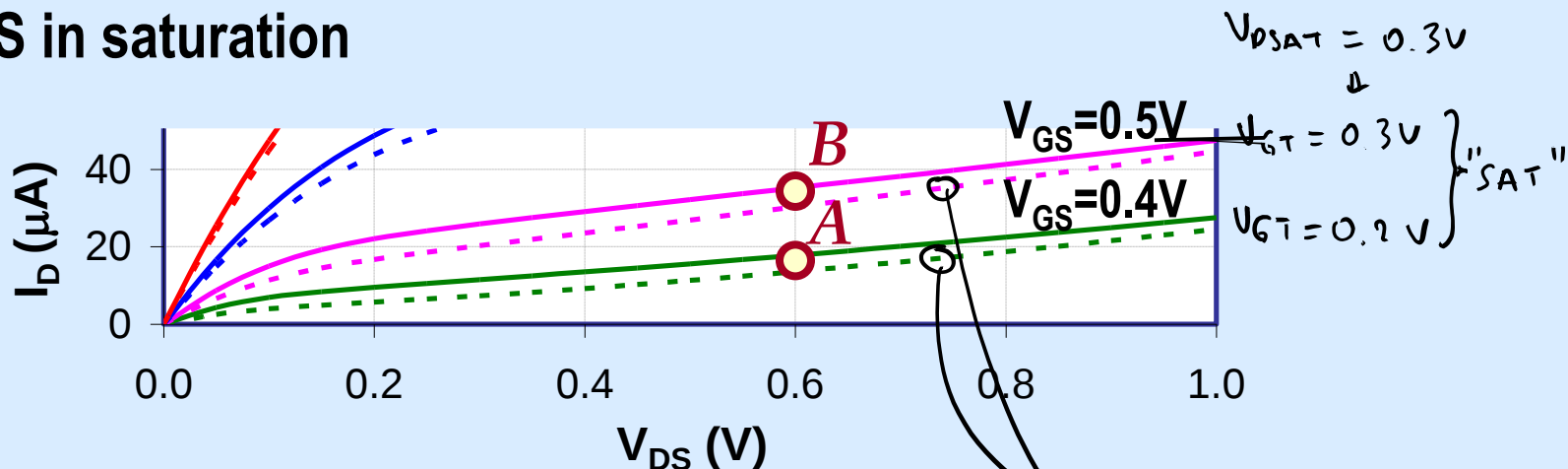
- ◆ **CLM term $(1 + \lambda V_{DS})$ also included for linear region**
 - Empirical, not grounded in physical considerations
- ◆ **Five parameters: V_{T0} , γ , V_{DSAT}^* , k' , λ**
 - Can determine from physics
 - Or choose values that best match simulation/measured data (match the best in regions that matter the most)
 - Use different model for $L \gg L_{min}$
(in EE115C we assume $L = L_{min}$ unless otherwise specified)

Let's see how do we extract these parameters from the I-V curves

The Meaning of Model Parameters: V_{T0}

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◆ MOS in saturation



★

$$\frac{I_A}{I_B} = \frac{(V_{GS_A} - V_{T0})^2}{(V_{GS_B} - V_{T0})^2} \Rightarrow \text{solve } \boxed{V_{T0}} \checkmark$$

with body bias ($V_{SB} > 0$)

The Meaning of Model Parameters: γ

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→ V_{TO} (see prev. slide)

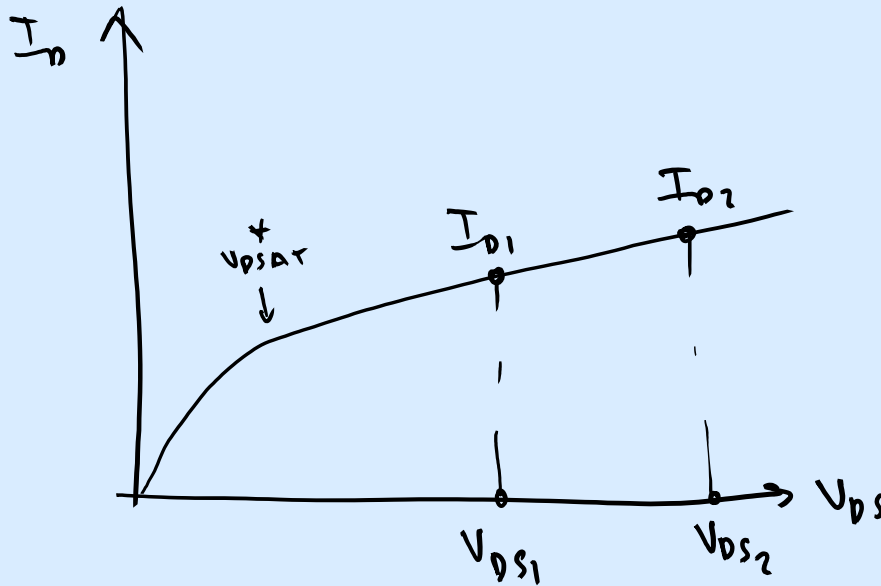
→ V_T for known V_{SB}

$$V_T = V_{TO} + \gamma \left(\sqrt{-2\phi_F + V_{SB}} - \sqrt{|2\phi_F|} \right)$$

↳ calc / estimate γ ✓

The Meaning of Model Parameters: λ

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$$\frac{I_{D1}}{I_{D2}} = \frac{1 + \lambda V_{DS1}}{1 + \lambda V_{DS2}}$$

$\Rightarrow$ calc λ ✓

The Meaning of Model Parameters: k'

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- assume V_{TO}, λ are known (from previous slides)

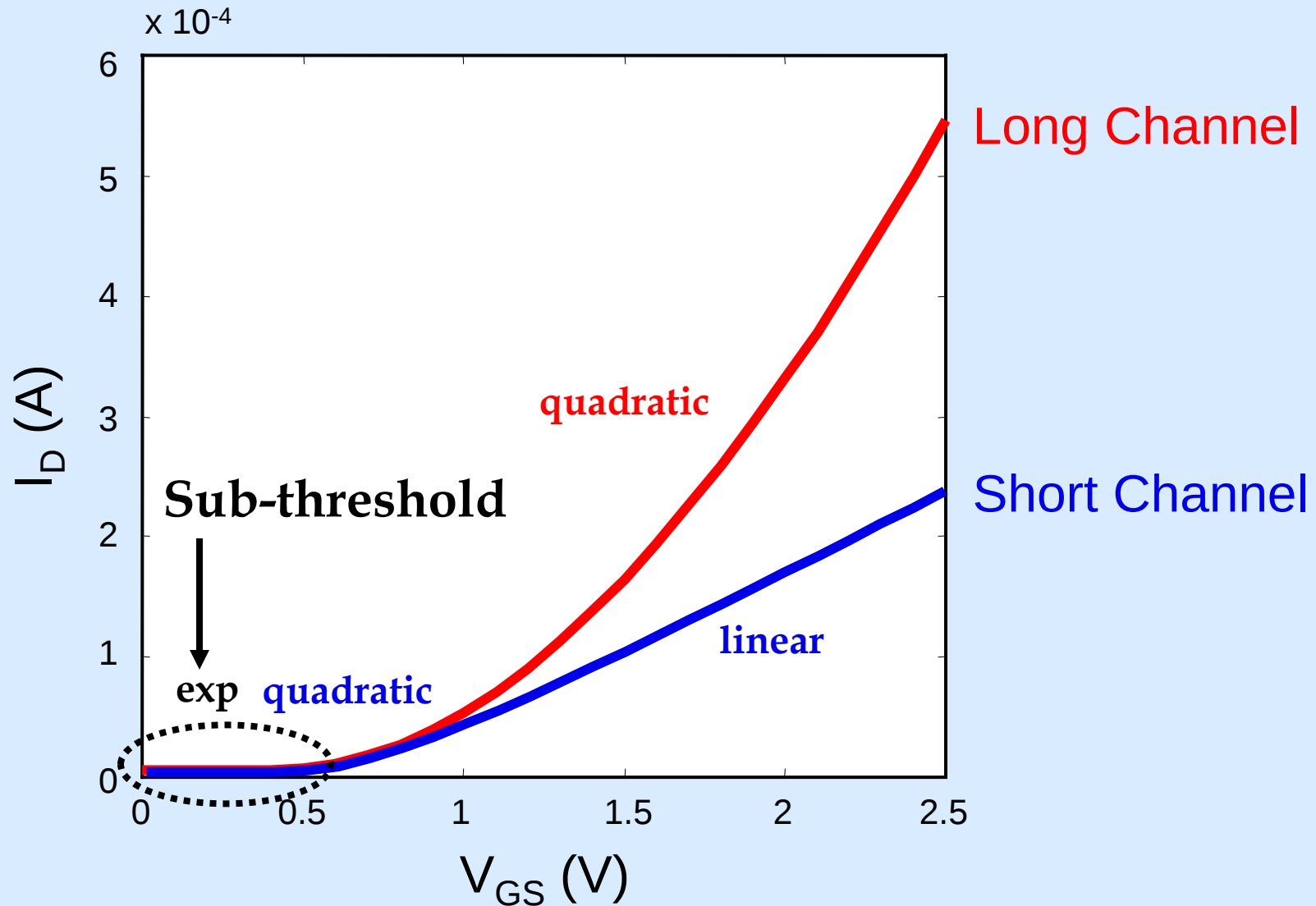
$$I_D = k' \frac{W}{L} V_{GT}^2 (1 + \lambda V_{DS})$$

$$\Rightarrow \boxed{k'} \checkmark$$

Sub-threshold Current

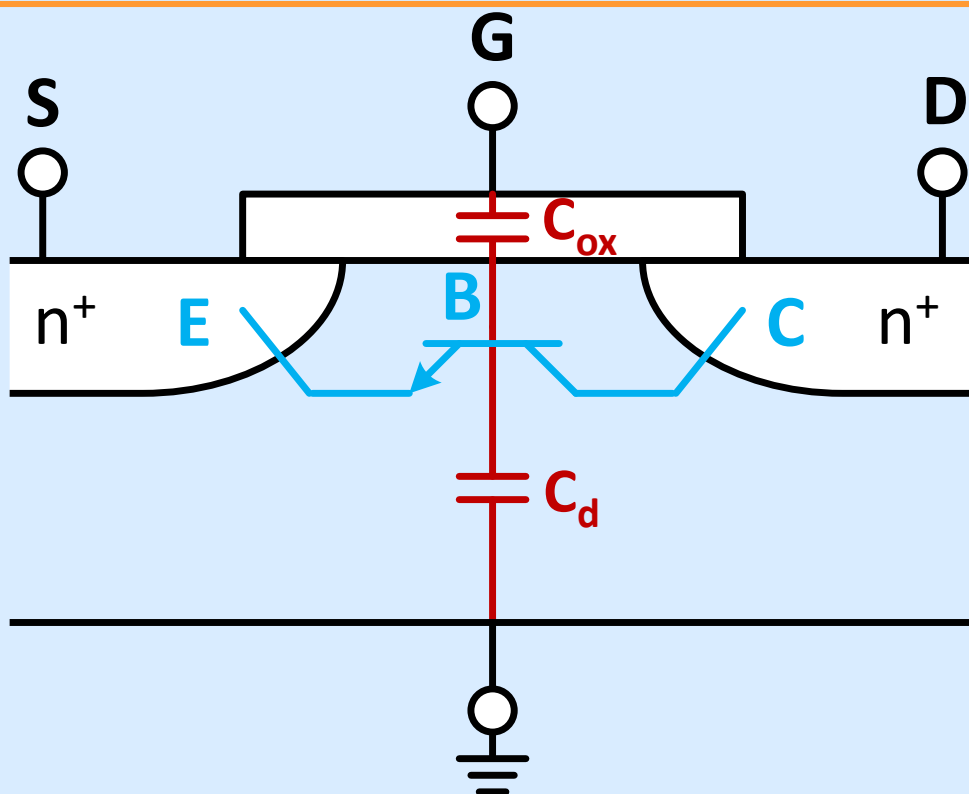
- ◆ **This is another topic of crucial importance in digital design (and not considered in EE115A/100 models)**
 - We need to consider sub-threshold current, because digital designs have many billions of transistors and when these are inactive, we may get some “surprise” power consumption

Sub-threshold I_D versus V_{GS} is Exponential 189



Modeling the Sub-threshold Behavior

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Parasitic BJT

$$I_C = I_0 e^{\frac{V_{BE}}{\Phi_t}}$$

$$V_{BE} = \frac{V_{GS}}{1 + \frac{C_d}{C_{ox}}}$$

$$n = 1 + \frac{C_d}{C_{ox}}$$

$$\Phi_t = \frac{kT}{q}$$

$$I_D = I_0 \cdot e^{\frac{V_{GS}}{n\Phi_t}} \cdot (1 - e^{-\frac{V_{DS}}{\Phi_t}})$$

Sub-threshold I_D vs. V_{GS}

*Physical
model*

$$I_D = I_0 \cdot \frac{W}{W_0} \cdot e^{\frac{V_{GS}}{n\Phi_t}} \cdot (1 - e^{-\frac{V_{DS}}{\Phi_t}})$$

$$I_0 = \underbrace{\mu \frac{W_0}{L} \Phi_t^2}_{I'_0} e^{-\frac{V_T}{n\Phi_t}}$$

DIBL

*Empirical
model*

$$I_D = I'_0 \cdot \frac{W}{W_0} \cdot 10^{\frac{V_{GS} - V_T + \gamma_D V_{DS}}{S}}$$

$$S = n\Phi_t \ln(10) \quad [\text{mV/dec}]$$

The Sub-threshold Slope Parameter

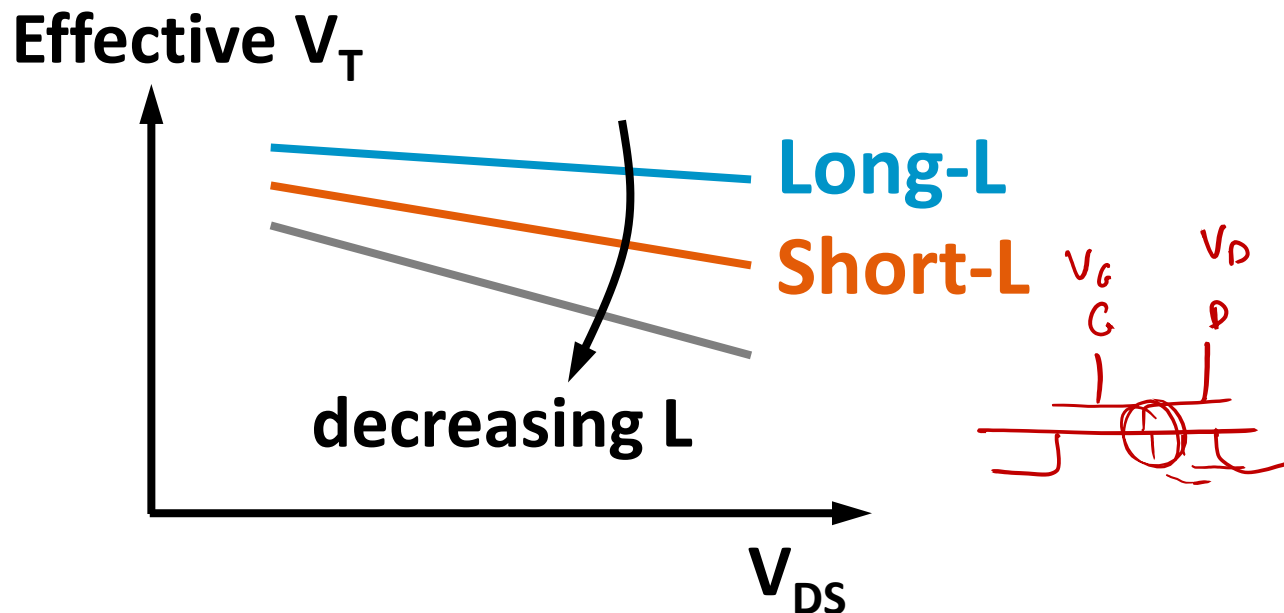
$$S = n\Phi_t \ln(10) \quad [\text{mV/dec}]$$

Change in V_{GS} that gives 10x change in I_{DS}

- ◆ $n = 1$ 60 mV/dec (ideal)
- ◆ $n = 1.5$ 90 mV/dec (typical)

- **S**: increases with temperature (Φ_t)
- **n**: intrinsic to device topology / structure

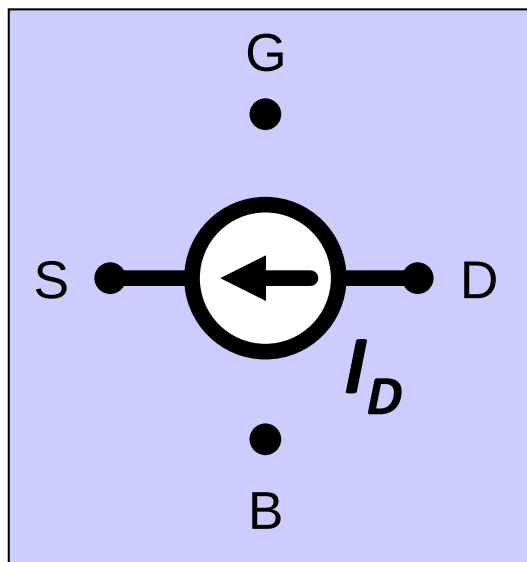
Drain Induced Barrier Lowering (DIBL)



- ◆ Field lines from the drain affect charge in the channel
- ◆ Typically derived for small V_{DS} , holds for large V_{DS}
 - Even if we neglect CLM, I_{DS} will increase b/c of V_T drop
 - Device turned off by V_{GS} (below V_T) may turn on by V_{DS}

MOS I-V Model: Subthreshold

$$V_{GT} = V_{GS} - V_T$$



Subthreshold region ($V_{GT} \leq 0$)

$$I_D = I_0' \cdot \frac{W}{W_0} \cdot 10^{\frac{V_{GS} - V_T + \gamma_D \cdot V_{DS}}{S}}$$

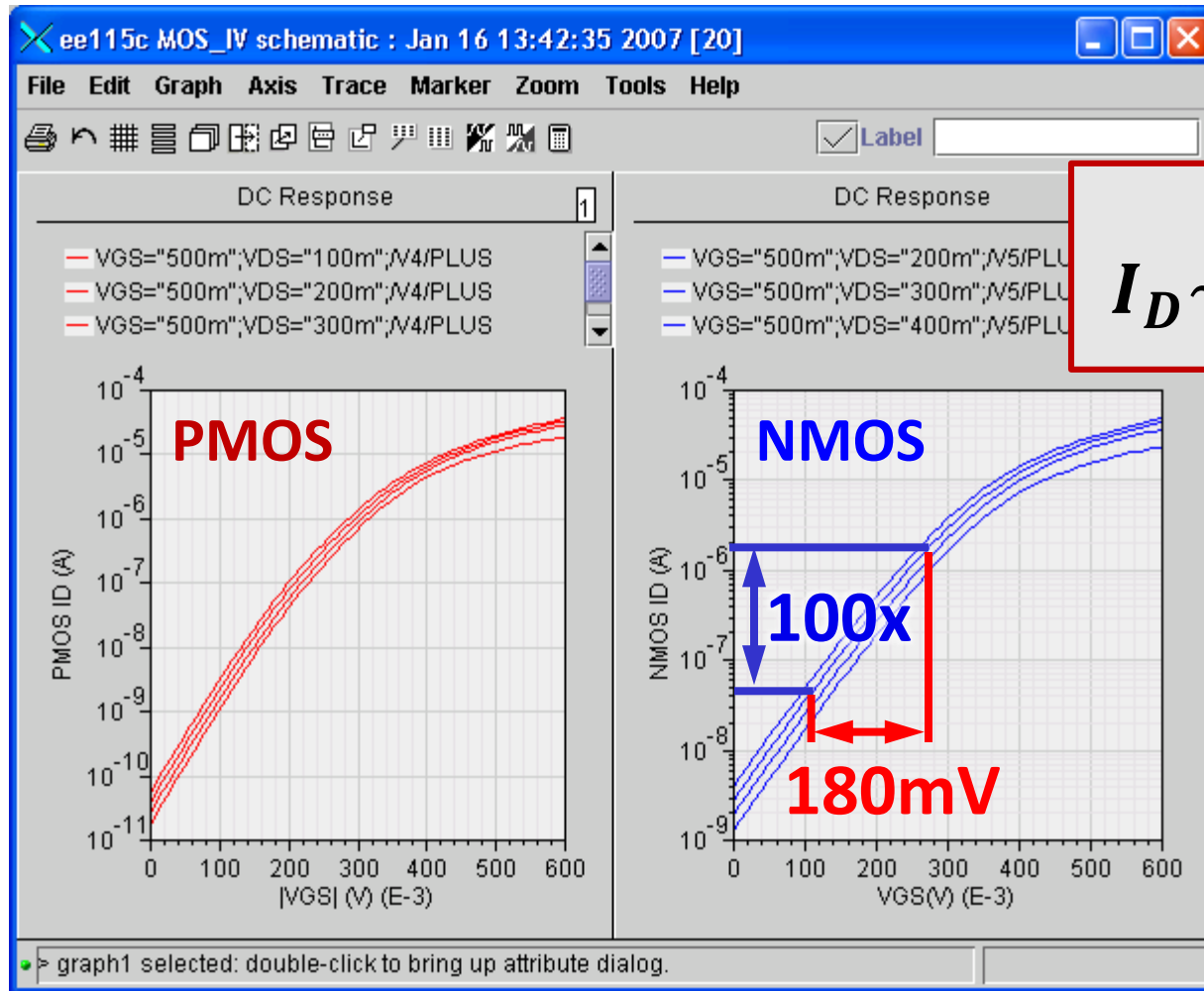
Model parameters

I_0' : Nominal leakage current

S : Subthreshold slope

γ_D : DIBL factor

90nm Simulation: Sub-threshold I_D vs. V_{GS}



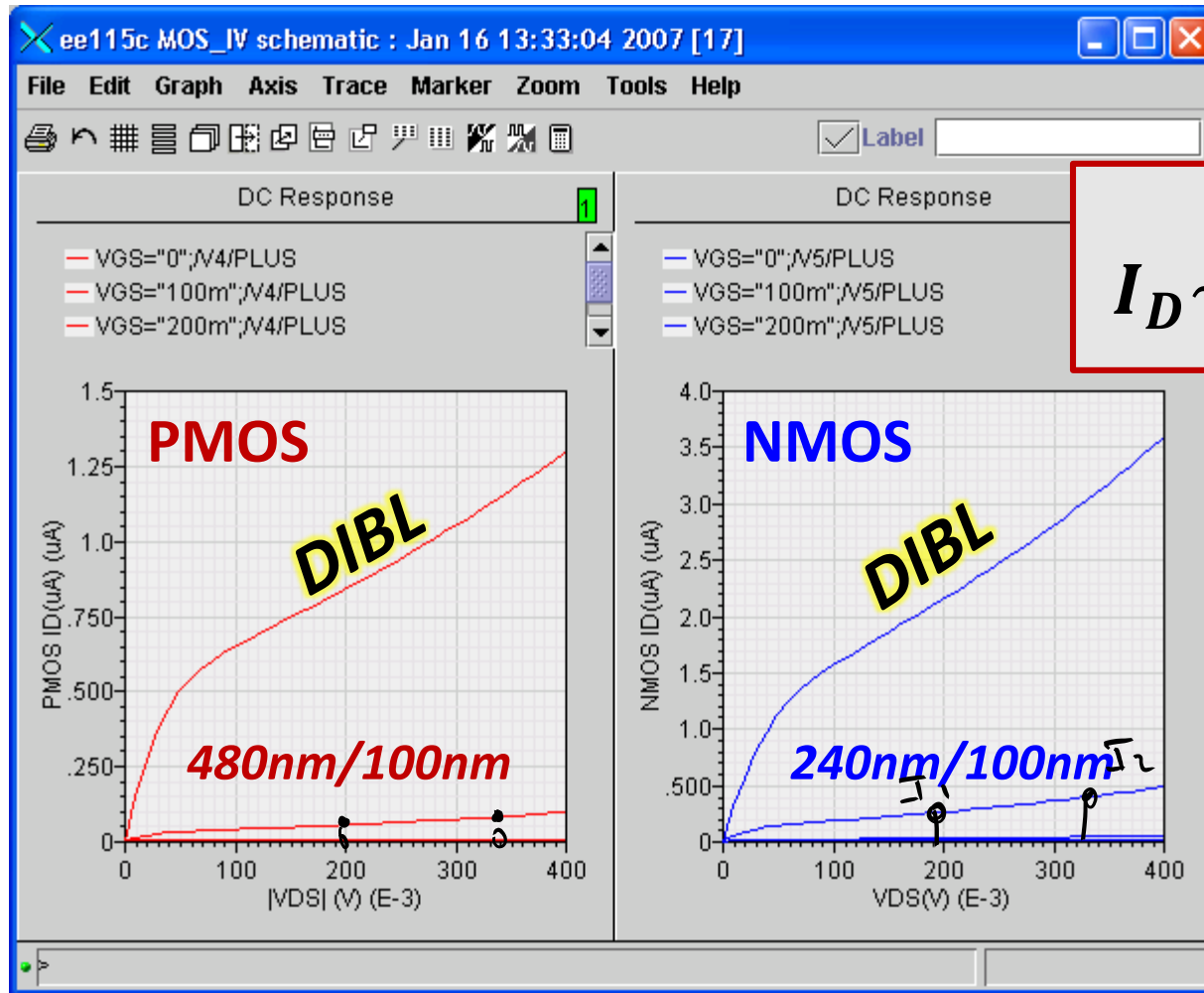
$$I_D \sim 10^{\frac{V_{GS} - V_T + \gamma_D V_{DS}}{S}}$$

$V_{DS} : 0 \text{ to } 0.4\text{V}$

$$S = n\Phi_t \ln(10)$$

90mV/dec

90nm Simulation: Sub-threshold I_D vs. V_{DS}



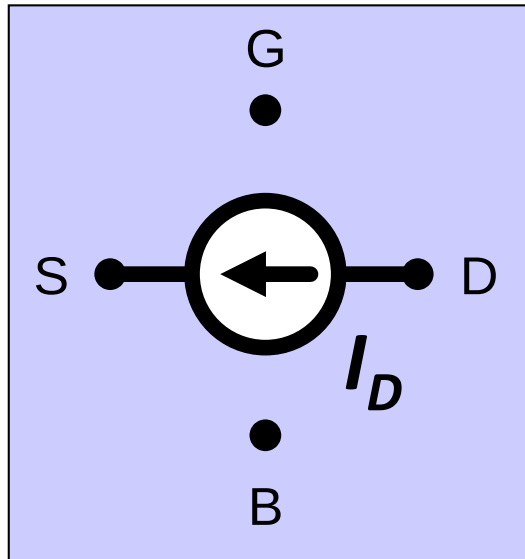
$$I_D \sim 10^{\frac{V_{GS} - V_T + \gamma_D V_{DS}}{S}}$$

$V_{GS} : 0 \text{ to } 0.3\text{V}$

γ_D DIBL

MOS I-V Model: Summary

$$V_{GT} = V_{GS} - V_T$$



Subthreshold region ($V_{GT} \leq 0$)

$$I_D = I_0' \cdot \frac{W}{W_0} \cdot 10^{\frac{V_{GS} - V_T + \gamma_D \cdot V_{DS}}{S}}$$

Active region ($V_{GT} \geq 0$) Lin, Sat, V-Sat

$$I_D = k' \cdot \frac{W}{L} \cdot \left(V_{GT} \cdot V_{min} - \frac{V_{min}^2}{2} \right) \cdot (1 + \lambda \cdot V_{DS})$$

$$V_{min} = \min(V_{DS}, V_{GT}, V_{DSAT}^*)$$

$\uparrow$ $\uparrow$ $\uparrow$
Lin "Sat" V-Sat

.MODEL Parameters MOS1 (Basic Parameters)

◆ .MODEL Modname NMOS/PMOS <VT0=VT0...>

Name	Parameter	Units	Default	Example	Scale Factor
VTO	Threshold voltage	V	0	1.0	—
KP	Transconductance parameter	AV^{-2}	2.0×10^{-5}	1.0E-3	—
GAMMA	Bulk threshold parameter	$\text{V}^{1/2}$	0	0.5	—
PHI	Surface potential	V	0.6	0.7	—
LAMBDA	Channel length modulation parameter	V^{-1}	0	1.0E-4	—
RD	Drain ohmic resistance	Ω	0	10	—
RS	Source ohmic resistance	Ω	0	10	—
RSR	D and S diffusion sheet resistance	Ω/sq	0	10	<i>NRD</i> <i>NRS</i>
CBD	Zero-bias BD junction capacitance	F	0	5P	—
CBS	Zero-bias BS junction capacitance	F	0	1P	—
CJ	Zero-bias bulk junction bottom capacitance	Fm^{-2}	0	2.0E-4	<i>AD</i> <i>AS</i>
MJ	Bulk junction grading coefficient	—	0.5	0.5	—
CJSW	Zero-bias bulk junction sidewall capacitance	Fm^{-1}	0	1.0E-9	<i>PD</i> <i>PS</i>
MJSW	Bulk junction grading coefficient	—	0.33	0.25	—
PB	Bulk junction potential	V	1	0.6	—
IS	Bulk junction saturation current	A	10^{-14}	1.0E-16	—
CGDO	GD overlap capacitance per unit channel width	Fm^{-1}	0	4.0E-11	<i>W</i>
CGSO	GS overlap capacitance per unit channel width	Fm^{-1}	0	4.0E-11	<i>W</i>
CGBO	GB overlap capacitance per unit channel length	Fm^{-1}	0	2.0E-10	<i>L</i>
TOX	Thin-oxide thickness	m	∞	0.1U	—
LD	Lateral diffusion	m	0	0.2U	—

In Reality: GPDk090 Model (gpdk090_mos.scs)

section TT_s1v

parameters

+ s1v_rs_ne =	0.000000e+000	s1v_vsath_ne =	1.120000e+005	s1v_pldd_surf =	6.000000e+019
+ s1v_uc1_ne =	3.700000e-010	s1v_u0_ne =	2.000000e-002	s1v_nch_ne =	5.200000e+017
+ s1v_rsc_ne =	4.082483e-014	s1v_cgbo_ne =	1.482000e-011	s1v_prt_ne =	1.000000e+001
+ s1v_rdc_ne =	4.082483e-014	s1v_vth0_ne =	1.692662e-001	s1v_k2_ne =	0.000000e+000
+ s1v_cgdo_ne =	2.667600e-010	s1v_ckappa_ne =	4.605336e+000	s1v_wint_ne =	6.000000e-009
+ s1v_k1_ne =	2.825346e-001	s1v_cgsl_ne =	1.111500e-010	s1v_nlidd_surf =	3.000000e+019
+ s1v_js_ne =	3.366667e-006	s1v_hdif_ne =	1.400000e-007	s1v_rdswh_ne =	3.900000e-006
+ s1v_jsw_ne =	3.366667e-010	s1v_tox_ne =	2.330000e-009	s1v_cj_ne =	7.983537e-004
+ s1v_cjsw_ne =	4.790122e-011	s1v_ldif_ne =	1.000000e-008	s1v_xj_ne =	2.500000e-008
+ s1v_rd_ne =	0.000000e+000	s1v_pb_ne =	9.918524e-001	s1v_cf_ne =	4.594612e-011
+ s1v_lint_ne =	1.500000e-008	s1v_cjswg_ne =	1.995884e-011	s1v_rsh_ne =	1.000000e+001
+ s1v_u0_pe =	1.200000e-002	s1v_nch_pe =	4.000000e+017	s1v_rsc_pe =	2.886751e-014
+ s1v_cgbo_pe =	1.392363e-011	s1v_rdc_pe =	2.886751e-014	s1v_vth0_pe =	-1.359511e-001
+ s1v_k2_pe =	0.000000e+000	s1v_cgdo_pe =	2.506253e-010	s1v_ckappa_pe =	1.043477e+001
+ s1v_wint_pe =	5.000000e-009	s1v_k1_pe =	2.637520e-001	s1v_cgsl_pe =	1.044272e-010
+ s1v_js_pe =	3.350000e-006	s1v_hdif_pe =	1.400000e-007	s1v_rdswh_pe =	7.800000e-006
+ s1v_jsw_pe =	3.350000e-010	s1v_tox_pe =	2.480000e-009	s1v_cj_pe =	7.912252e-004
+ s1v_cjsw_pe =	4.747351e-011	s1v_ldif_pe =	1.000000e-008	s1v_xj_pe =	2.500000e-008
+ s1v_rd_pe =	0.000000e+000	s1v_pb_pe =	1.009805e+000	s1v_cf_pe =	4.527118e-011
+ s1v_lint_pe =	1.500000e-008	s1v_cjswg_pe =	1.978063e-011	s1v_rsh_pe =	2.000000e+001
+ s1v_rs_pe =	0.000000e+000	s1v_vsath_pe =	1.000000e+005		

include "gpdk090_mos.scs" section = s1v_mos

endsection TT_s1v

This model continues on the next slide

GPDK090 Model (section s1v_mos)

```
section s1v_mos
model gpdk090_nmos1v bsim3v3 type = n
+ lmin = 0.0          lmax = 1.0          wmin = 0.0
+ wmax = 1.0          tnom = 25.0         version = 3.2
+ tox = s1v_tox_ne    toxm = s1v_tox_ne    xj = s1v_xj_ne
+ nch = s1v_nch_ne    lln = 1.0000000    lwn = 1.0000000
+ wln = 1.0000000     wwn = -1.0000000    lint = s1v_lint_ne
+ ll = 0.0            lw = 0.0            lwl = 0.0
+ wint = s1v_wint_ne  wl = 0.0            ww = 0.0
+ wwl = 0.0            mobmod = 1          binunit = 2
+ xl = 0              xw = 0              dwg = 0.0
+ dwb = 0.0            acm = 12            ldif = s1v_ldif_ne
+ hdif = s1v_hdif_ne  rsh = s1v_rsh_ne    rd = s1v_rd_ne
+ rs = s1v_rs_ne       rsc = s1v_rsc_ne    rdc = s1v_rdc_ne
+ vth0 = s1v_vth0_ne  k1 = s1v_k1_ne    k2 = s1v_k2_ne
+ k3 = -2.3000000     dvt0 = 3.86366    dvt1 = 1.2
+ dvt2 = 5.0299990E-02 dvt0w = 0.0          dvt1w = 0.0
+ dvt2w = 0.0          nlx = 1.2517999E-07 w0 = -7.1353000E-09
+ k3b = 0.5576769     ngate = 4.0E20        vsat = s1v_vsats_ne
+ ua = -6.1879500E-10 ub = 1.8806652E-18    uc = 1.3823546E-10
+ rdsw = s1v_rdsw_ne  prwb = 0.0          prwg = 0.0
+ wr = 1.0000000      u0 = s1v_u0_ne    a0 = 2.3750000
+ keta = -3.1429991E-02 a1 = 0.0          a2 = 0.9900000
+ ags = 0.8900000     b0 = 0.0          b1 = 0.0
```

And many more parameters... (compare to our 5-parameter model)

Spectre Netlist (NMOS, PMOS)

section s1v_mac

subckt s1v_ckt_nch (n11 n2 n33 n4)

parameters l=0.1u w=10u multi=1 factor=1 nrd=s1v_hdif_ne/factor/w nrs=s1v_hdif_ne/factor/w

+ Tox_ratio = 3.0e-9 / (s1v_tox_ne*s1v_tox_ne*s1v_tox_ne)

MAIN (n1 n2 n3 n4) **gpdk090_nmos1v** w=w l=l nrd=nrd nrs=nrs multi=multi

GDF1 (n2 n1) bsource i = w*0.6*s1v_xj_ne*4.97232*Tox_ratio*v(n2,n1)*v(n2,n3)*exp(-4.85669e11*s1v_tox_ne*...

GDF2 (n2 n3) bsource i = w*0.6*s1v_xj_ne*4.97232*Tox_ratio*v(n2,n3)*sqrt((v(n2,n3) - 0.026*log(4.0e20 ...

20 / s1v_nldd_surf)) + 1.0e-4)*exp(-4.85669e11*s1v_tox_ne*(0.43-0.054*sqrt((v(n2,n3) - 0.026*log(4.0e20 ...

.0e20 / s1v_nldd_surf)) + ... - 0.026*log(4.0e20 / s1v_nldd_surf))*(v(n2,n3) ...s1v_nldd_surf)) + 1.0e-4)))

rdn (n1 n11) resistor r= 6.8 *nrd/multi

rsn (n3 n33) resistor r= 6.8 *nrs/multi

ends s1v_ckt_nch

subckt s1v_ckt_pch (p11 p2 p33 p4)

parameters l=0.1u w=10u multi=1 factor=1 nrd=s1v_hdif_pe/factor/w nrs=s1v_hdif_pe/factor/w

+ Tox_ratio = 3.0e-9/(s1v_tox_pe*s1v_tox_pe*s1v_tox_pe)

MAIN (p1 p2 p3 p4) **gpdk090_pmos1v** w=w l=l nrd=nrd nrs=nrs multi=multi

GDF1 (p2 p1) bsource i = w*0.6*s1v_xj_pe*3.42537*Tox_ratio*v(p2, p1)*sqrt((v(p2, p1)-

0.026*log(9.32E19/s1v_pldd_surf))*(v(p2, p1)-0.026*log(9.32E1

9/s1v_pldd_surf)) + 1.0e-4)*exp(-7.0645e11*s1v_tox_pe*(0.31-0.024*sqrt((v(p2, p1)-

0.026*log(9.32E19/s1v_pldd_surf))*(v(p2, p1)-0.026*log(9.32E19... s1v_pldd_surf)) + 1.0e-4))*(1.0+0.03*sqrt((v(p2, p1)-

0.026*log(9.32E19/s1v_pldd_surf))*(v(p2, p1)-0.026*log(9.32E19/s1v_pldd_surf)) + 1.0e-4)))

GDF2 (p2 p3) bsource i = w*0.6*s1v_xj_pe*3.42537*Tox_ratio*...sqrt((v(p2, p3)-...0.026*log(9.32E19/...)) + 1.0e-4)))

rdp (p1 p11) resistor r = 7.1 * nrd / multi

rsp (p3 p33) resistor r = 7.1 * nrs / multi

ends s1v_ckt_pch

endsection s1v_mac

Technology Scaling

◆ Scaling parameters

- Geometry: W , L , t_{ox}
- Voltage: V_{DD} , V_T

◆ Constant voltage

- Scale only geometry by S (~ 1.4)

◆ Constant electric field

- Scale geometry and voltage by S (~ 1.4)

◆ General

- Scale geometry by S
- Scale voltage by U
- $S > U$